



IPW

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Docket No: Q79837

Ken MIYAGI, *et al.*

Appln. No.: 10/773,294

Group Art Unit: 1752

Confirmation No.: 8731

Examiner: John S. Y. CHU

Filed: February 9, 2004

For: PHENOL NOVOLAK RESIN, PRODUCTION PROCESS THEREOF, AND POSITIVE
PHOTORESIST COMPOSITION USING THE SAME

AMENDMENT UNDER 37 C.F.R. § 1.111 AND STATEMENT OF SUBSTANCE OF INTERVIEW

MAIL STOP AMENDMENT

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed November 16, 2005, please amend the above-identified application as follows on the accompanying pages.

TABLE OF CONTENTS

AMENDMENTS TO THE CLAIMS	2
REMARKS	3